

Attorney's Docket No.: 10559-895001/P17799

Listing of Claims

This listing of claims replaces all prior versions, and listings, of claims in the application:

Claims 1-19. (Canceled)

20. (New) A lithography method comprising:
placing a pellicle comprising polyvinylidene fluoride
(PVDF) on a side of a lithography mask; and
transmitting an electromagnetic radiation through the
pellicle to form a lithographic image on a substrate.

21. (New) The method of claim 20, wherein placing the
pellicle on the side of the lithography mask comprises placing a
pellicle comprising a copolymer of PVDF on the side of the
lithography mask.

22. (New) The method of claim 21, wherein placing the
pellicle comprises placing a pellicle comprising a block
copolymer of PVDF on the side of the lithography mask.

23. (New) The method of claim 21, wherein placing the
pellicle comprises placing a pellicle comprising a copolymer of
PVDF and an amorphous fluoropolymer on the side of the
lithography mask.

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24. (New) The method of claim 23, wherein placing the pellicle comprises placing a pellicle comprising a copolymer of PVDF and a cyclic fluorocarbon oxygen-containing polymer on the side of the lithography mask.

25. (New) The method of claim 23, wherein placing the pellicle comprises placing a pellicle comprising a copolymer of PVDF and a polyimide linear fluoropolymer on the side of the lithography mask.

26. (New) The method of claim 23, wherein placing the pellicle comprises placing a pellicle comprising a copolymer of PVDF and a perfluorinated polyether on the side of the lithography mask.

27. (New) The method of claim 23, wherein placing the pellicle comprises placing a pellicle comprising a copolymer of PVDF and a combination of two or more of a cyclic fluorocarbon oxygen-containing polymer, a polyimide linear fluoropolymer, and a polyimide linear fluoropolymer on the side of the lithography mask.

28. (New) The method of claim 20, wherein placing the pellicle on the side of the lithography mask comprises placing a fluorinated pellicle on the side of the lithography mask.

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29. (New) The method of claim 20, wherein placing the pellicle on the side of the lithography mask comprises placing a surface-modified pellicle on the side of the lithography mask.

30. (New) The method of claim 20, wherein placing the pellicle on the side of the lithography mask comprises stretching the pellicle over a frame above a surface of the mask.

31. (New) The method of claim 20, wherein transmitting the electromagnetic radiation comprises transmitting one or more of ultraviolet and far ultraviolet through the pellicle.

32. (New) The method of claim 20, further comprising spinning a solution that includes PVDF on a substrate.

33. (New) The method of claim 20, further comprising correcting for a change in transmissivity of the pellicle to the electromagnetic radiation.

34. (New) The method of claim 33, wherein correcting for the change in transmissivity of the pellicle comprises correcting for the change in transmissivity only after the pellicle has been exposed to more than about 12 J/cm² of 157 nm wavelength radiation.

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35. (New) The method of claim 33, wherein correcting for the change in transmissivity of the pellicle comprises correcting for the change in transmissivity only after the pellicle has been exposed to more than about 40 J/cm² of 157 nm wavelength radiation.

36. (New) The method of claim 20, further comprising:
stepping to a second position relative to the substrate;
and

transmitting the electromagnetic radiation through the pellicle to form a second copy of the lithographic image on the substrate.